

Title (en)

AN APPARATUS FOR ANALYZING THE CHARACTERISTICS OF A SEMICONDUCTOR WAFER AND METHOD OF OPERATING SAID APPARATUS

Title (de)

VORRICHTUNG ZUR ANALYSE DER EIGENSCHAFTEN EINES HALBLEITERWAFERS UND METHODE ZUR VERWENDUNG DER VORRICHTUNG

Title (fr)

DISPOSITIF PERMETTANT D'ANALYSER LES CARACTERISTIQUES D'UNE GALETTE DE SEMI-CONDUCTEUR ET METHODE D'UTILISATION DUDIT DISPOSITIF

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Application

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Abstract (en)

[origin: WO9902970A1] An optical measurement system is disclosed for evaluating samples with multi-layer thin film stacks. The optical measurement system includes a reference ellipsometer and one or more non-contact optical measurement devices. The reference ellipsometer is used to calibrate the other optical measurement devices. Once calibration is completed, the system can be used to analyse multi-layer thin film stacks. In particular, the reference ellipsometer provides a measurement which can be used to determine the total optical thickness of the stack. Using that information coupled with the measurements made by the other optical measurement devices, more accurate information about individual layers can be obtained.

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